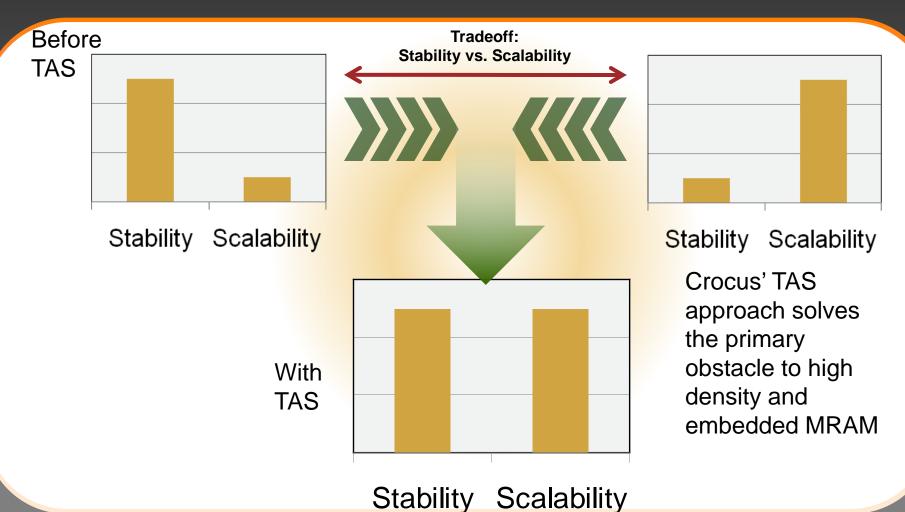


"MLU" Magnetic Logic Unit Architecture

Barry Hoberman Chief Marketing Officer Crocus Technology August 2011

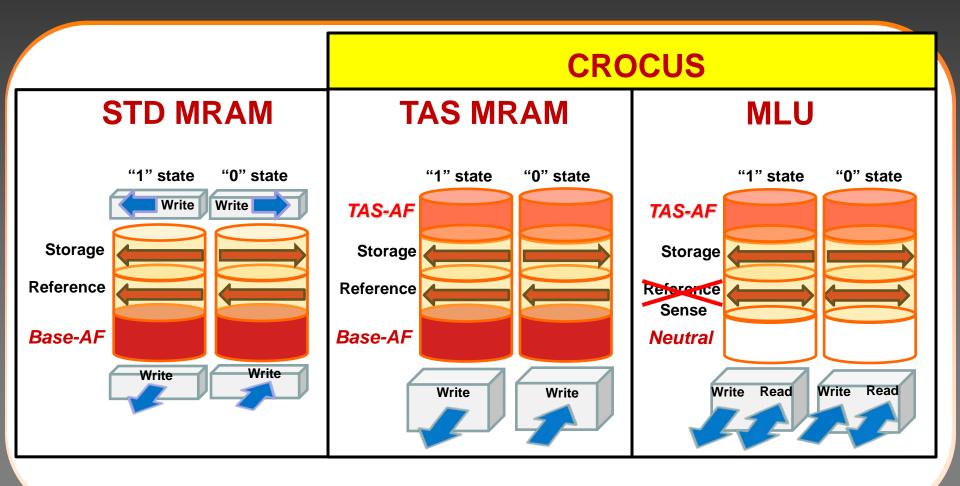
Thermally Assisted Switching (TAS) The Heart of MLU



CROCUSTechnology Blossoming future



Progression to MLU







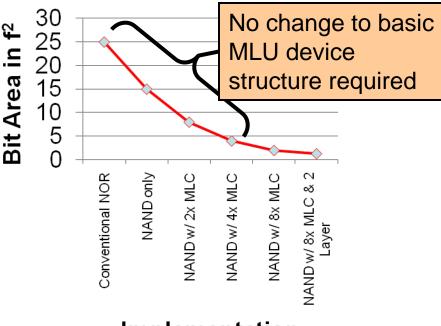




MLU Impact on Memory Density

TAS
ArchitectureBit
DensityConventional
NOR~25 f²NAND1.5-3x
densityMLC2-8
bits/cellMulti-layer2+ layers

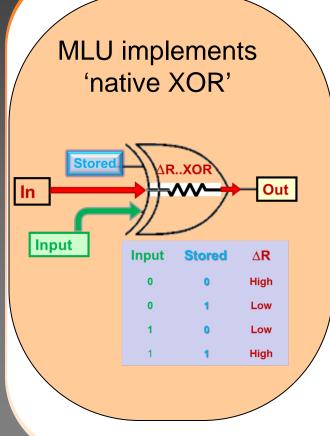
Cell Size per bit



Implementation



MLU Impact on Logic Implementation





MLU Impact on Device Operation and Manufacturing

High Temperature

>200° C NVM operation Reference pinning layer removed

Simplified Manufacturing

No magnetic anneal Reduced cost – reference pin layer

Enhanced Yield

Self-differential reading Relieve magnetic device parameter constraints >5x σ window imprvm't

CROCUSTechnology Blossoming future MLU Summary

• MLU:

- Makes very high density MRAM possible
 - NAND and MLC are straightforward
- Opens new logic applications for magnetic memory
 - CAM, Secure Memory, Pattern Matching, Look-up Table
- Removes previous technology barriers
 - High temp NVM operation, greatly expanded yield window, lower cost wafer processing